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# TABLE OF CONTENTS

WHAT THE GLOBAL ECONOMIC OUTLOOK* IMPLIES FOR SEMICONDUCTORS .....	1
<i>D. Meldrum</i>	
CHALLENGES IN NEXT GENERATION SEMICONDUCTOR MANUFACTURING .....	15
<i>K. Lee</i>	
CHEMICAL QUALITY IN ADVANCED FAB PROCESSES .....	24
<i>J. Hemphill</i>	
WET PROCESSES AT THE LEADING EDGE .....	32
<i>S. Jones</i>	
CONTROLLING STATIC ELECTRICITY DURING SINGLE WAFER WET CLEANING PROCESSES .....	42
<i>K. Chang, D. Kim, H. Kim, S. Lee, Y. Ko</i>	
CLEANING MATERIALS MARKET .....	56
<i>D. Maloney</i>	
FUTURE OF MATERIALS: A HOLISTIC PERSPECTIVE` .....	65
<i>J. O'Neill</i>	
ENABLING SUSTAINABLE SEMICONDUCTOR MANUFACTURING APPLYING FIRST PRINCIPLES TO CONTAMINATION CONTROL AND SITE WATER MANAGEMENT .....	75
<i>S. Libman</i>	
SURFACTANT RINSE SOLUTION FOR EUV PHOTO-LITHOGRAPHIC PROCESS.....	90
<i>P. Liao, M. Park, J. Tsai, J. Chin, P. Hsu</i>	
EFFECT OF POWER AND SURFACTANT ON THE BEHAVIOR OF BUBBLES IN AN ULTRASONIC FIELD .....	91
<i>B. Sahoo, S. Han, N. Yerriboina, K. Ando, B. Kang, A. Klipp, J.-G. Park</i>	
ADVANCED SOLUTIONS FOR IMPROVED POST-CMP CLEANING OF CERIA-BASED RESIDUES .....	92
<i>K. Gramigna, P. Bernatis, W. Huang, F. Yeh</i>	
NEW FORMULATION FOR IMPROVED POLYSILICON POST-CMP CLEAN.....	93
<i>P. Tzeng, K. Gramigna, W. Huang, P. Bernatis, L. Chang, A. Tang, V. Wu, K. Chin</i>	
SYNTHESIS AND APPLICATIONS OF QUATERNARY AMMONIUM HYDROXIDES FOR SEMICONDUCTOR PROCESSES .....	94
<i>H. Zhou, A. Yan, V. White, K. Zhang, J. Henderson, G. Gibson, T. Clark</i>	

## Author Index